



THERMCO-EPITAXY EPIPRO FAMILY OF SILICON EPITAXY DEPOSITION SOLUTIONS

The EpiPro family of systems meeting the industry's need for high throughput processing with low cost of ownership for epitaxial processing.

Dual station batch silicon epitaxy deposition solutions designed to meet todays demanding production requirements offering both manually loading / unloading and fully automatized wafer handling solutions.

Combining leading edge technology, process capability with field-proven capability.

- High Process Flexibility
- P and N doped material
- Substrates from 100 to 200mm
- Wide EPI Layer thickness5 µm to > 100 µm
- EPI Layer Resistivity from 0.02 Ω cm to 50 Ω cm
- Dual process chamber systems
- IG systems with dual RF supply for induction heaters
- · Low Cost of Ownership
- Unique dopant injection system
- Patented chamber features
- EpiPro 5000 : Manual solution
- EpiPro 8000 : Automated solution

Thermco Systems have thermal process tools designed with your emerging technologies in mind

EPIPRO FAMILY:

- EpiPro 5000: Manually loaded / unloaded. Dual reactor with inductive coil heating systems and single switching RF generator source.
- **EpiPro 5000IG:** Manually loaded / unloaded. Dual reactor with inductive coil heating systems and dedicated RF generator source for each reactor for higher throughput.
- EpiPro 8000: Automated loaded / unloaded. Dual reactor with inductive coil heating systems and single switching RF generator source.
- **EpiPro 8000IG:** Automated loaded / unloaded. Dual reactor with inductive coil heating systems and dedicated RF generator source for each reactor for higher throughput.





Upgraded PLC control system with Windows OS touch screen GUI. Now offering SECS / GEM interface.





TYPICAL THROUGHPUT COMPARISON:

150 mm		
Thickness	EpiPro 5000 EpiPro 8000	EpiPro 5000IG EpiPro 8000IG
15 µm	22.7 w/hr	26.8 w/hr
35 µm	18.8 w/hr	23.9 w/hr
60 µm	15.4 w/hr	21.0 w/hr
100 µm	12.0 w/hr	17.6 w/hr

200 mm		
Thickness	EpiPro 5000 EpiPro 8000	EpiPro 5000IG EpiPro 8000IG
15 µm	10.1 w/hr	11.9 w/hr
35 µm	8.3 w/hr	10.6 w/hr
60 µm	6.9 w/hr	9.3 w/hr
100 μm	5.3 w/hr	7.8 w/hr